Poster Presentation

[FMCp3]Metrology &Manufacturing

Thu. Nov 28, 2019 10:40 AM - 1:10 PM Main Hall (1F)

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[FMCp3-6]High Resolution Technologies of 1.0 μ m L/S Using PSM Specialized in DUV Broadband Illumination

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Keywords:Lithography, FPD, High resolution, DUV, Phase shift mask

To meet the demands for high resolution, we designed a PSM specialized in DUV broadband illumination and evaluated resolution performance with the PSM. In this paper, we present the ability of 1.0 μ m L/S pattern resolution with our PSM based on simulation results and exposure test results.